



Division of Finance
Purchasing

ADDENDUM #1

September 28, 2026

RE: Bid Number 50012-665-27: Purchase of an Electron Beam Lithography (EBL) System

The following information is provided to amend the original invitation to bid on September 18, 2026.

- **The following questions were posed by a potential vendor. This addendum addresses those questions and provide supplemental information related to this solicitation:**

Does the University require a purpose-built/dedicated electron beam lithography instrument, or will a field-emission SEM equipped with a fully integrated third-party EBL pattern-generation, beam-blanking, alignment, and control system be considered compliant, provided the complete system meets all stated specifications?

We will consider bids that are FE-SEMs with integrated EBL capabilities, provided that they meet all stated specifications.

For the requirement to write patterns over areas up to approximately 3 mm × 3 mm or larger, is this acceptable through automated stage movement and stitching of multiple write fields?

Yes, that is acceptable.

For the stated 100 nm resolution requirement, does this refer to minimum achievable lithographic feature size/patterning resolution?

Yes.

All other specifications remain unchanged.

Sincerely,

Clint Williams
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